

**AN IMPROVED CPL MASK AND A METHOD AND PROGRAM PRODUCT FOR
GENERATING THE SAME**

ABSTRACT

A method of generating a mask for printing a pattern including a plurality of features. The method includes the steps of obtaining data representing the plurality of features; and forming at least one of the plurality of features by etching a substrate to form a mesa and depositing a chrome layer over the entire upper surface of the mesa, where said mesa has a predetermined height.